

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	525222	(interconnect\$6 or wiring or metalliz\$6 or metal) and semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/12 13:04
L3	64446	2 and (SiO2 or SiO?sub\$3 or ((Si or silicon) adj (oxide or dioxide))) and (SiN or Si3N4 or SiN\$1 or (Si?sub\$3 adj N?sub\$3) or ((Si or silicon) adj nitride))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/12 13:08
L4	22384	3 and (@ad<="19970204" or @rlad<="19970204")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/12 13:07
L5	7095	(SiO2 or SiO?sub\$3 or ((Si or silicon) adj (oxide or dioxide))) same (SiN or Si3N4 or SiN\$1 or (Si?sub\$3 adj N?sub\$3) or ((Si or silicon) adj nitride)) same (stress\$6 or strain\$6 or crack\$6 or peel\$6 or adhes\$6 or wrinkl\$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/12 13:10
L6	1758	5 and 4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/12 13:11